U.S.S.N.: 10/600,974

Response to Office Action

Page 3 of 17

Amendments to the Claims

This listing of claims will replace all prior versions, and listing, of claims in the application.

Listing of Claims:

1. (Currently Amended) A semiconductor laser device employed in an optical pickup of
a 3-beam method that divides one laser beam into three beams by an optical system, said three
beams being a 0th-order beam and \pm first order beams, and directs the three beams towards an
optical recording medium to detect information recorded on said recording medium and detecting
tracking error information during said detection by the 0th-order beam and ± first order beams
reflected from said recording medium, wherein said optical system comprises:
a header portion, said header portion including a mount surface and a leading edge plane
that crosses a plane defined by the mount surface;
a laser chip for generating the said one laser beam, the laser chip being mounted to the
mount surface of said header portion;
a reflector, the reflector being wherein a reflector is attached on a side beam incident
region of the a-leading end plane of said a header portion and heing configured and arranged so
as to reflect said side beam outside said optical system, where the mounted with a laser chip
emitting said laser beam, said side beam is being one of two side beams generated by said
$reflected \pm first$ order beam and fed back through said optical system returning towards said
header portion to strike said side beam incident region; and, said reflector reflecting said side
beam outside said optical system
wherein said reflector is constituted of a material having different properties that that of

U.S.S.N.: 10/600,974

Response to Office Action Page 4 of 17

material constituting the header portion.

2. (Original) The semiconductor laser device according to claim 1, wherein said reflector

is attached at the leading end plane of the header portion so that a distance between a reflecting

plane of said reflector and a light emitting point at an outgoing end plane of said laser chip is at

least 50 μ m and not more than 150 μ m.

3. (Original) The semiconductor laser device according to claim 1, wherein said

reflecting plane of said reflector is tilted having an angle of at least 10 degrees with respect to a

plane perpendicular to a main beam generated by said 0th-order beam and fed back through said

optical system.

4. (Original) The semiconductor laser device according to claim 1, wherein said reflector

has a cross section of a saw-toothed configuration, and includes an inclination plane of a plurality

of steps.

5. (Currently Amended) The semiconductor laser device according to claim 1, wherein

the material constituting said reflector is formed of any one of a synthetic resin and metal.

6. (Original) The semiconductor laser device according to claim 5, wherein said

synthetic resin includes a thermosetting resin.

U.S.S.N.: 10/600,974

Response to Office Action

Page 5 of 17

7. (Original) The semiconductor laser device according to claim 5, wherein said metal

includes a metal of a hardness lower than the hardness of the metal forming the header portion.

8. (Original) A method of fabricating a the semiconductor laser device recited in claim 1

employed in an optical pickup of a 3-beam method that divides one laser beam into three beams

by an optical system, said optical system including a header portion that includes a mount surface

and a leading edge plane that crosses a plane defined by the mount surface; a laser chip for

generating the said one laser beam and being mounted to the mount surface of said header

portion; and a reflector that is attached on a side beam incident region of the leading end plane of

said header portion and being configured and arranged so as to reflect said side heam outside the

ontical system, where the said side beam is one of two side beams generated by said reflected ±

first order beam and fed back through said ontical system returning towards said header portion

to strike said side heam incident region, said fabricating method comprising the steps of:

attaching at said side beam incident region at the a leading end plane of said header

portion a base material of a reflector formed of a metal that is softer than the metal forming said

header portion; and or a synthetic resin prior to curing, and then

shaping said attached base material into a reflector of a predetermined configuration so as

to reflect said side beam outside the optical system.

Claims 9-18 Canceled

U.S.S.N.: 10/600,974 Response to Office Action

Page 6 of 17

19. (New) The fabricating method of claim 8, wherein said shaping includes shaping the

reflector so a reflecting plane of said reflector is configured and arranged so a distance between

the reflecting plane and a light emitting point at an outgoing end plane of said laser chip is at

least 50 µm and not more than 150 µm.

20. (New) The fabricating method of claim 19, wherein said shaping includes shaping

the reflector so the reflector plane is configured and arranged so as to be titled at an angle of at

least 10 degrees with respect to a plane perpendicular to a main beam generated by said 0th-order

beam.

21. (New) The fabricating method of claim 8, wherein said shaping includes shaping the

reflector so as to form a plurality of inclined planes.

22. (New) A method of fabricating a semiconductor laser device employed in an optical

pickup of a 3-beam method that divides one laser beam into three beams by an optical system,

said optical system including a header portion that includes a mount surface and a leading edge

plane that crosses a plane defined by the mount surface; a laser chip for generating the said one

laser beam and being mounted to the mount surface of said header portion; and a reflector that is

attached on a side beam incident region of the leading end plane of said header portion and being

configured and arranged so as to reflect said side beam outside the optical system, where the said

U.S.S.N.: 10/600,974

Response to Office Action

Page 7 of 17

side beam is one of two side beams generated by said reflected ± first order beam and fed back through said optical system returning towards said header portion to strike said side beam incident region, said fabricating method comprising the steps of:

attaching at said side beam incident region at the leading end plane of said header portion a base material of a reflector formed of a synthetic resin prior to curing, and then shaping said attached base material into a reflector of a predetermined configuration so as to reflect said side beam outside the optical system.

- 23. (New) The fabricating method of claim 22, wherein said shaping includes shaping the reflector so a reflecting plane of said reflector is configured and arranged so a distance between the reflecting plane and a light emitting point at an outgoing end plane of said laser chip is at least 50 μm and not more than 150 μm .
- 24. (New) The fabricating method of claim 23, wherein said shaping includes shaping the reflector so the reflector plane is configured and arranged so as to be titled at an angle of at least 10 degrees with respect to a plane perpendicular to a main beam generated by said 0th-order beam.
- 25. (New) The fabricating method of claim 22, wherein said shaping includes shaping the reflector so as to form a plurality of inclined planes.

U.S.S.N.: 10/600,974

Response to Office Action

Page 8 of 17

26. (New) The semiconductor laser device of claim 1, wherein the reflector is

configured and arranged so as to be smaller in dimension that said leading edge plane but

sufficient to intercept and reflect the said side beam.

27. (New) The semiconductor laser device according to claim 1, wherein said material

constituting the reflector is a synthetic resin and a reflective material filler.

28. (New) The semiconductor laser device according to claim 1, wherein said reflector is

constituted of a reflectance- reducing material, the reflectance reducing material including one

type of an epoxy resin and an UV resin and a non-reflective filler being at least one type of silica

and carbon powder as a filler.